



SHEET 1 OF 1

| INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449) | | | ATTY. DOCKET NO. 55071-267 | | SERIAL NO. 10/626,858 | | |
|---|-------------|---|-------------------------------------|--|---|-------------|----|
| | | | APPLICANT Stephen D. HSU, et al. | | | | |
| | | | FILING DATE July 25, 2003 | | GROUP 2826 | | |
| U.S. PATENT DOCUMENTS | | | | | | | |
| EXAMINER'S INITIALS | CITE NO. | Document Number Number-Kind Code ² (if known) | Publication Date MM-DD-YYYY | Name of Patentee or Applicant of Cited Document | Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear | | |
| SP | | US 5,881,125 | 03/09/1999 | Dao | | | |
| SP | | US 6,625,802 B2 | 09/23/2003 | Singh et al. | | | |
| SP | | US 6,553,562 B2 | 04/22/2003 | Capodieci et al. | COL: 3, 4, 5, 8, 17 | | |
| SP | | US 2002/168107 A1 | 11/07/2002 | Van Os Lodewijk | | | |
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| FOREIGN PATENT DOCUMENTS | | | | | | | |
| EXAMINER'S INITIALS | CITE NO. | Foreign Patent Document Country Codes - Number - Kind Codes (if known) | Publication Date MM-DD-YYYY | Name of Patentee or Applicant of Cited Document | Pages, Columns, Lines Where Relevant Figures Appear | Translation | |
| | | | | | | Yes | No |
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| OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | | |
| EXAMINER'S INITIALS | CITE NO. | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | | | | | |
| SP | | HSU, Stephen D., et al. "65 nm Full-chip implementation Using Double Dipole Lithography." Optical Microlithography XVI, Santa Clara, California, USA, February 2003, Proceedings of the SPIE- The International Society for Optical Engineering, pp. 215-231, XP 009024366, ISSN: 0277-786X | | | | | |
| SP | | HSU, Stephen D., et al. "Dipole Decomposition Mask-design for full Chip Implementation at the 100nm Technology Node and Beyond." Proceedings of the SPIE, US, Volume 4691, pp. 476-490, XP 002261072, ISSN: 0277-786X | | | | | |
| SP | | TORRES, J.A., et al. "Model Assisted Double Dipole Decomposition." Proceedings of the SPIE, Volume. 4691, pp. 407-417, XP 002257323 ISSN: 0277-786X | | | | | |
| SP | | LIM, Chang-Moon., et al. "Intra-field CD Variation by Stray Light from Neighboring Field." Optical Microlithography XV, Santa Clara, California, USA, March 2002, Proceedings of the SPIE- The International Society for Optical Engineering, 2002, pp.1412-1420, XP 002268484, ISSN: 0277-786X | | | | | |
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| EXAMINER <i>Quinn Parihar</i> | | | | DATE CONSIDERED NOV 1, 2005 | | | |

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.